

WHAT IS CLAIMED IS:

1-45. (Cancelled)

46. (New) An apparatus for holding a substrate, said apparatus comprising:

a table;

protrusions, being provided on said table, on which the substrate is to be supported; and

at least a portion of an attracting unit, said attracting unit attracting the substrate onto said protrusions,

wherein said apparatus is arranged such that said protrusions are disposed in accordance with a pattern formed on or to be formed on the substrate.

47. (New) An apparatus according to claim 46, wherein the pattern is one of an alignment mark, a shot region, a die region, and a scribe line formed on or to be formed on the substrate.

48. (New) An apparatus according to claim 46, wherein an attracting force of said attracting unit is adjustable in accordance with regions on the substrate.

49. (New) An apparatus according to claim 46, wherein said apparatus is an exposure apparatus and further comprises an exposure unit for exposing the substrate to a pattern of an original.

50. (New) A method of manufacturing a device, said method comprising the steps of:  
holding a substrate by use of an apparatus as recited in claim 46; and  
processing the substrate held by the apparatus.

51. (New) An apparatus for holding a substrate, said apparatus comprising:  
a chuck for supporting the substrate;  
a stage for holding said chuck; and  
a conveyance unit for conveying said chuck onto said stage,  
wherein said chuck conveyed by said conveyance unit is selected on the basis  
of information related to protrusions, being provided on said chuck, for supporting the  
substrate, and information related to a pattern formed on or to be formed on the substrate.

52. (New) An apparatus according to claim 51, wherein the pattern is one of an  
alignment mark, a shot region, a die region, and a scribe line formed on or to be formed on  
the substrate.

53. (New) An apparatus according to claim 51, further comprising an attracting unit  
for attracting the substrate onto said chuck, wherein an attracting force of said attracting unit  
is adjustable in accordance with regions on the substrate.

54. (New) An apparatus according to claim 51, wherein said apparatus is an exposure apparatus and further comprises an exposure unit for exposing the substrate to a pattern of an original.

55. (New) A method of manufacturing a device, said method comprising the steps of:  
holding a substrate by use of an apparatus as recited in claim 51; and  
processing the substrate held by the apparatus.